

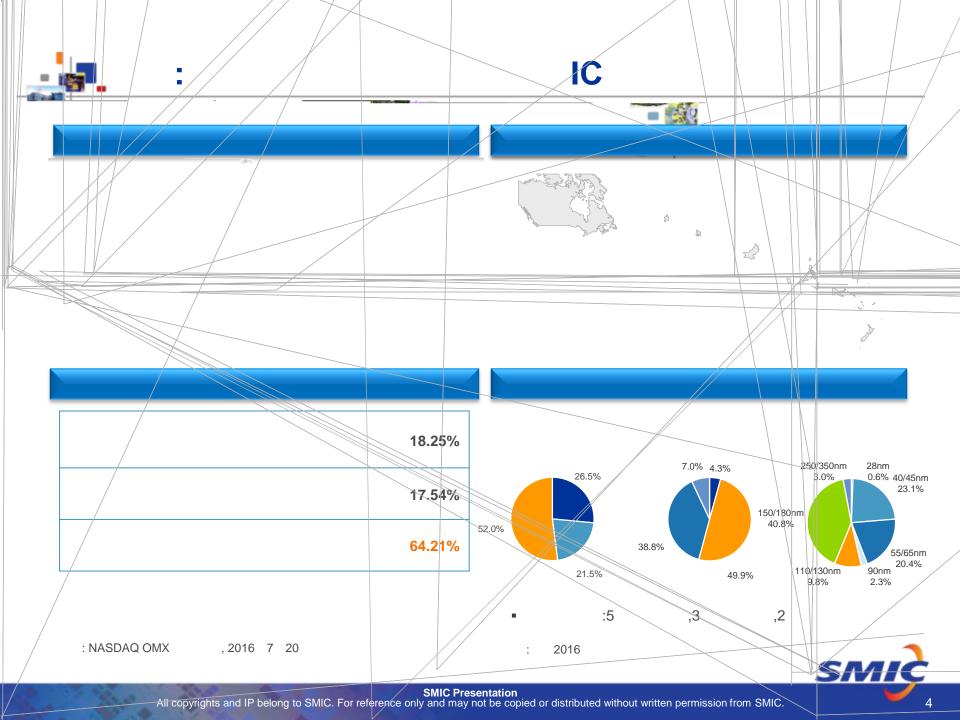
SMI

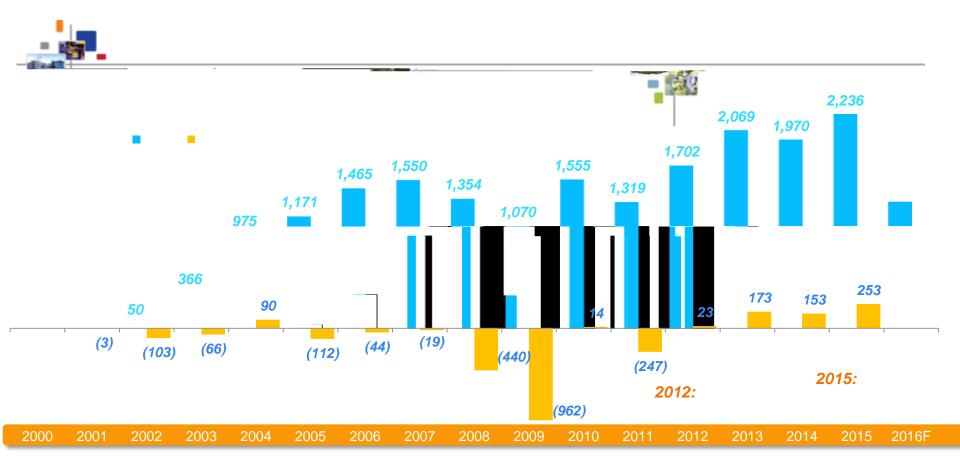
0981-HK

1995

1995

20-F 6-K









2009-2015

William Tudor Brown

Cadence Design Systems, Inc.

> 2013 ,

(NEA)











- **2008 2009:**
- **2002** 2008:





NEC **2009 2011:**

■ 2007 2009: Silterra Malaysia

2005 2006: **2001 2005**: **1996 2001:**

■ 1984 1996: AT&T







































2016 2



: 2

: 31.6%

5

: \$16.7%

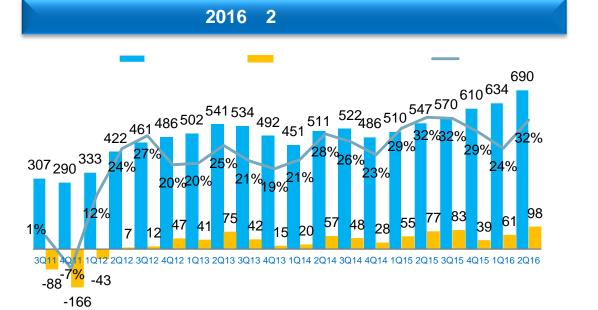


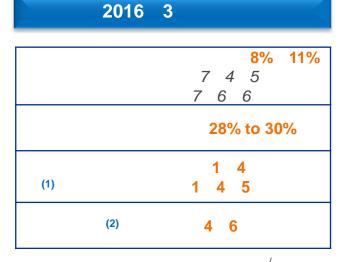
17

: 19

: 52.0%,

: 97.9%

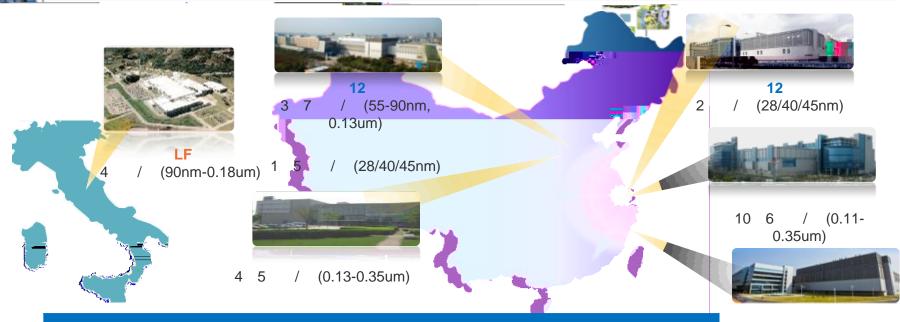












	2	2016	
45nm	20K	20K	~20K
55-90nm, 0.13um	37K	45K	~50K
45nm	15K	18K	~35K
0.11-0.35um	106K	-	~106K
0.13-0.35um	45K	-	~45K
0.15-0.35um	26K	31K	~50K
90nm-0.18um	40K	-	~50K



(0.15-0.35um)

2 6

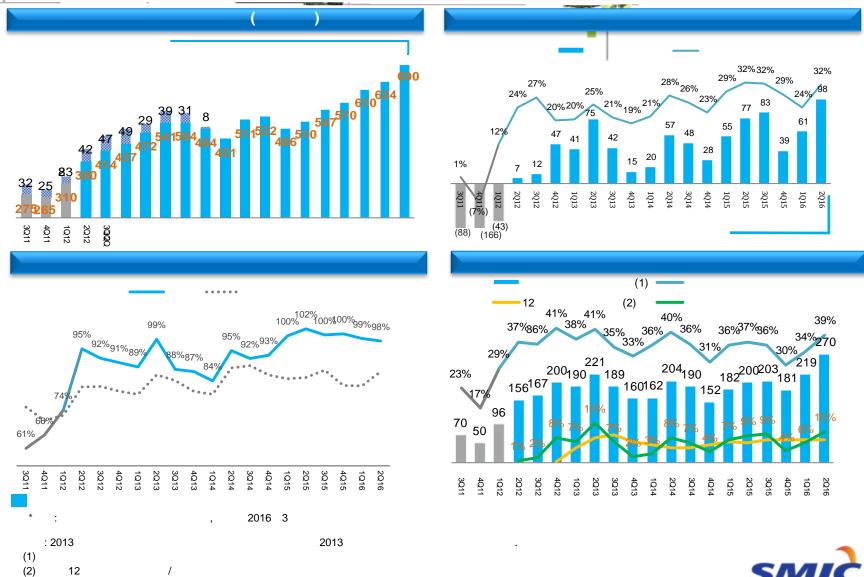


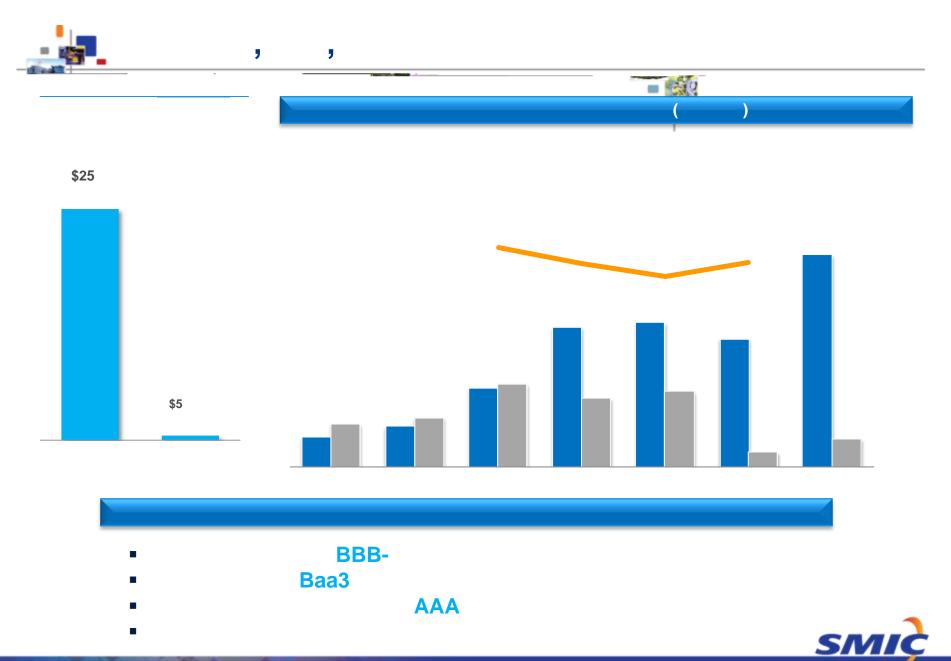


- 口简介
- 中芯业绩
- 口中国半导体行业机遇
- □获利成长战略
- □总结







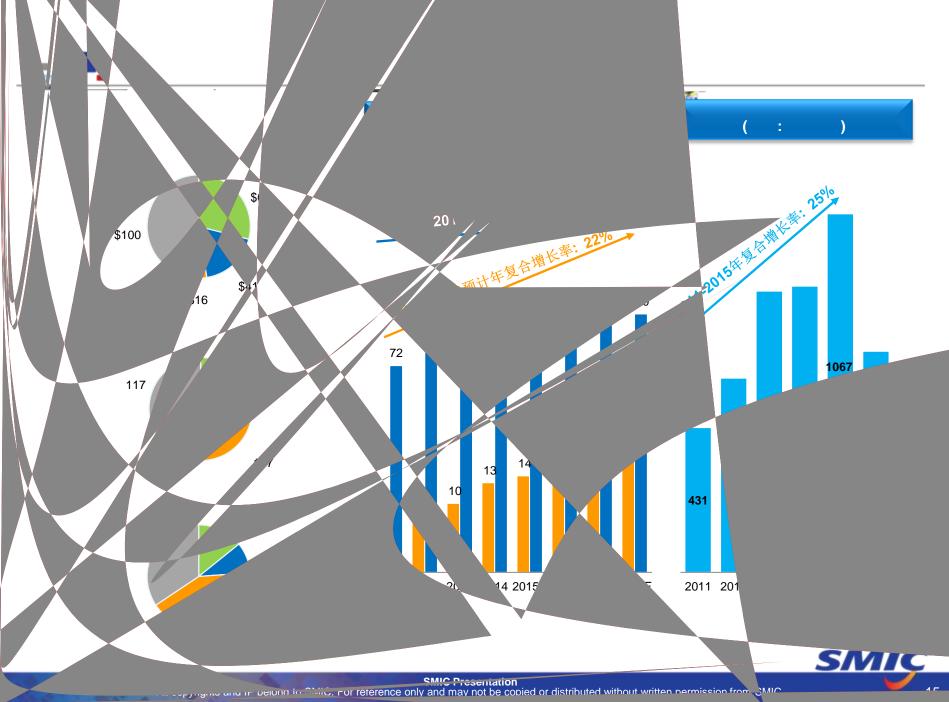






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- □总结













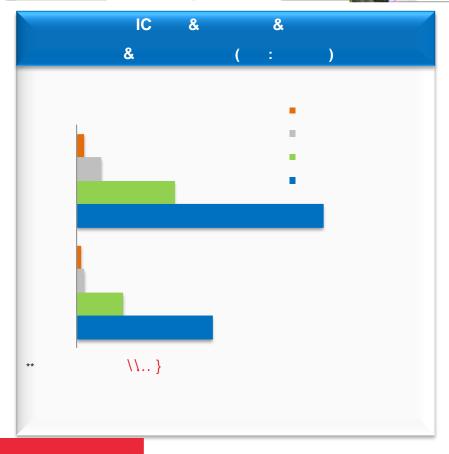


die Tre



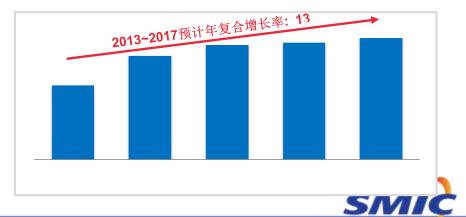


IC













- 口简介
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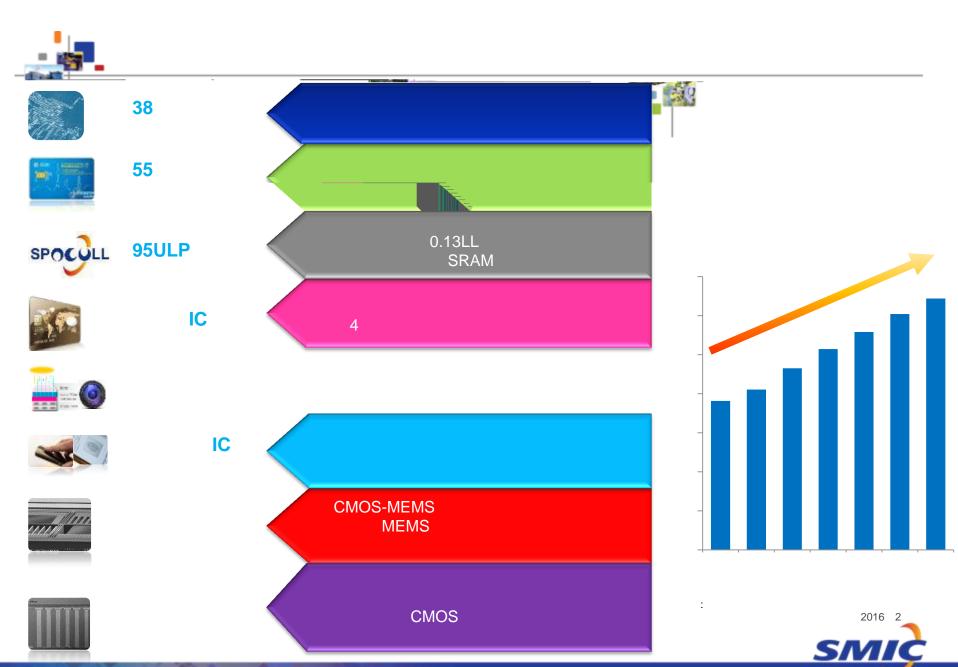








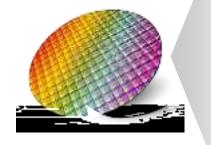












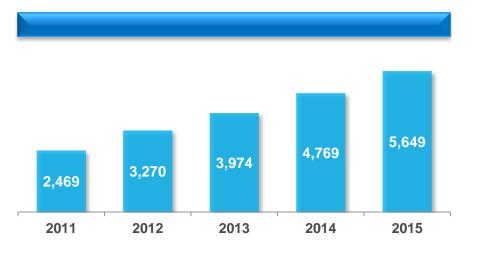
- 8 0.13LL 0.13LL SRAM

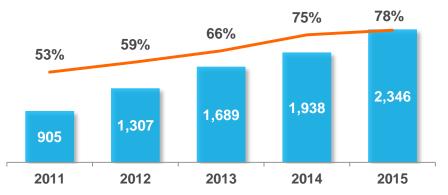
■ SPOCULL --- <u>SMIC POly Contact for Ultra Low Leakage</u>

















- 口简介
- 口中芯业绩
- □中国半导体行业机遇
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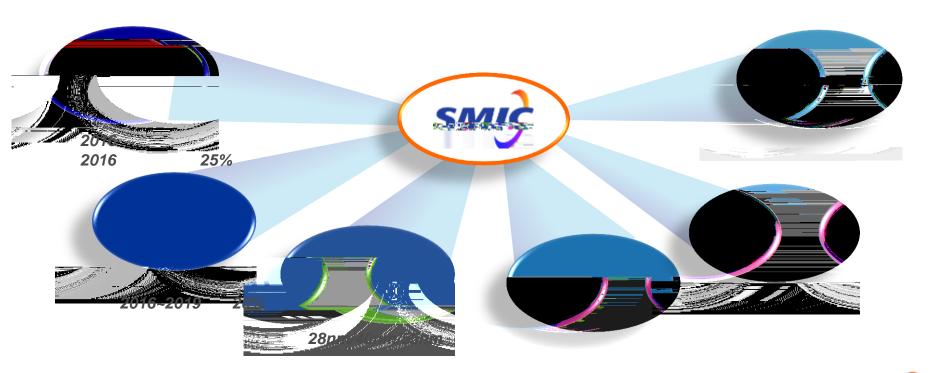






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: ir@smics.com

